

IN THE SPECIFICATION:

Page 4, line 21 to Page 5, line 2, please amend as follows:

The gas supply unit 19 supplies gas containing sulfur hexafluoride (SF_6) and helium (He) mixed in a volume ratio ranging from 1:1 to 1:10 as the plasma-generating gas. The mixing ratio of sulfur hexafluoride to helium is determined primarily according to an etching rate and visual quality of the etched side (the polished side). ~~When the~~ A high mixing ratio of sulfur hexafluoride ~~is high~~ (i.e. $\text{SF}_6:\text{He}=1:1$) ~~, the~~ increases ~~the etching rate increases, thereby decreasing~~ and decreases the visual quality due to a hazy etched side. ~~When the~~ A low mixing ratio of sulfur hexafluoride ~~is low~~ (i.e., $\text{SF}_6:\text{He}=1:10$) ~~, the~~ increases the visual quality with a mirror-like etched surface ~~decreases, thereby decreasing~~ and decreases the etching rate.